



<b>Session Title:</b>	<b>[ThE2] Modeling Etch Processes</b>
<b>Session Date:</b>	<b>November 14 (Thu.), 2024</b>
<b>Session Time:</b>	<b>10:50-12:20</b>
<b>Session Room:</b>	<b>Room E (Sicily Room, 1F, Paradise Hotel Busan)</b>
<b>Session Chair:</b>	<b>Prof. Heeyeop Chae (Sungkyunkwan Univ., Korea)</b>

**[ThE2-1] [Invited]** **10:50-11:20**

**Thermal Atomic Layer Etching Mechanism of Aluminum Oxide: A First Principle Study**

Khabib Khumaini, Gyejun Cho, Hye-Lee Kim, and Won-Jun Lee (Sejong Univ., Korea)

**[ThE2-2]** **11:20-11:40**

**Ab Initio Investigation of Chelation on  $\text{CoCl}_2$  Films for Atomic Layer Etching**

Eugene Huh and Sangheon Lee (Ewha Womans Univ., Korea)

**[ThE2-3]** **11:40-12:00**

**Computational Study of Re-deposition Effects due to Geometric Differences in MASK Patterns in High Aspect Ratio Plasma Etching**

Byeong-Yeop Choi, Si-Jun Kim, Won-Nyoung Jeong, Young-Seok Lee, In-Ho Seong, Chul-Hee Cho, Min-Su Choi, Seong-Hyun Seo, Woo-been Lee, and Shin-Jae You (Chungnam Nat'l Univ., Korea)

**[ThE2-4]** **12:00-12:20**

**A Unified Global Model Accompanied with a Voltage and Current Sensor for Low-Pressure Capacitively Coupled RF Discharge**

Inho Seong, Sijun Kim, Woobeen Lee, Youngseok Lee, Chulhee Cho, Wonnyoung Jeong, Minsu Choi, Byeongyeop Choi, Huichan Seo, Sangheon Song, and Shinjae You (Chungnam Nat'l Univ., Korea)